

GP/1762
PATENT

9-2-02

Case Docket No. SEPP17.001AUS

Date: July 26, 2002

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s)

Ninisto et al.

Appl. No.

10/067,634

Filed

February 4, 2002

For

METHOD OF DEPOSITING

RARE EARTH OXIDE THIN

FILMS

Examiner

Unknown

Group Art Unit:

1762

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July 26, 2002

Adeal S Akhtar Reg No 41 394

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TRANSMITTAL LETTER

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ATTENTION: APPLICATION BRANCH

Dear Sir:

Enclosed for filing in the above-identified application are:

- (X) An Information Disclosure Statement.
- (X) A PTO Form 1449 with Thirteen (13) references.
- (X) The Commissioner is hereby authorized to charge any additional fees which may be required, or credit any overpayment, to Account No. 11-1410.

(X) Return prepaid postcard.

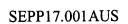
Adeel S. Akhta

Registration No. 41,394

Attorney of Record

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INFORMATION DISCLOSURE STATEMENT

United States Patent and Trademark Office P.O. Box 2327 Arlington, VA 22202

Dear Sir:

Enclosed is form PTO-1449 listing 13 references that are also enclosed. This Information Disclosure Statement is being filed before the receipt of a first Office Action on the merits, and presumably no fee is required in accordance with 37 C.F.R. § 1.97(b)(3). If a first Office Action on the merits was mailed before the mailing date of this Statement, the Commissioner is authorized to charge the fee set forth in 37 C.F.R. § 1.17(p) to Deposit Account No. 11-1410.

Respectfully submitted, KNOBBE, MARTENS, OLSON & BEAR, LLP

Dated: _	July	176	2002	E

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EXAMINER

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